



ITW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Justin K. Brask et al.

Serial No.: 10/622,955

Filed: July 18, 2003

For: Etching Metal Silicides  
and Germanides

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Art Unit: 2811

Examiner: Sara W. Crane

Atty Docket: ITL.1021US  
P16708

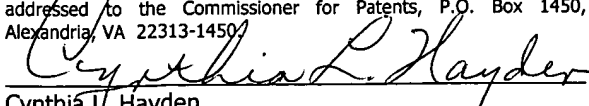
Assignee: Intel Corporation

Mail Stop **Amendment**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY TO PAPER NO. 052005**

Sir:

In response to the office action mailed June 3, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: August 3, 2005  
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.  
  
Cynthia L. Hayden